

REMARKS

The present application was filed on August 5, 2003 with claims 1 through 30. Claims 10 and 16 were cancelled, without prejudice, in the Amendment and Response to Office Action dated February 25, 2005. Claim 31 was added in the Supplemental Amendment dated April 27, 2005. Claims 1-9, 11-15, and 17-31 are presently pending in the above-identified patent application. The Examiner, however, indicates in the Office Action Summary that claims 1-30 are presently pending.

In the Office Action, the Examiner rejected claims 1-30 under 35 U.S.C. §102(b) as allegedly being anticipated by U.S. Patent No. 6,087,064 issued to Lin et al. (hereinafter "Lin"), and under 35 U.S.C. §103(a) as allegedly unpatentable over U.S. Patent No. 6,506,497 issued to Kennedy et al. (hereinafter "Kennedy") in view of U.S. Patent No. 6,521,699 issued to Feder et al. (hereinafter "Feder").

Independent Claims 1, 21, 30 and 31

Independent claims 1, 21, 30, and 31 were rejected under 35 U.S.C. §102(b) as allegedly being anticipated by Lin, and under 35 U.S.C. §103(a) as allegedly unpatentable over Kennedy in view of Feder. Regarding claim 1, the Examiner asserts that Lin teaches novel silsesquioxane polymers that are useful in negative photoresist compositions and photolithographic processes. The Examiner also acknowledges that Kennedy fails to specifically mention a cross-linking agent, but asserts that Feder discloses a layer similar to that of Kennedy and teaches that polysilsesquioxane compositions conventionally comprise cross-linking agents.

Applicants note that the independent claims of the present invention are directed to an antireflective hardmask composition. Lin, alternatively, teaches the *use of a compound as a photo imageable material*. Independent claims 1, 21, 30, and 31 require a fully condensed polyhedral oligosilsesquioxane, $\{\text{RSiO}_{1.5}\}_n$, wherein n equals 8; and at least one chromophore moiety and transparent moiety for use as an *antireflective hardmask composition*. Applicants also note that neither Kennedy nor Feder disclose or suggest a fully condensed polyhedral oligosilsesquioxane, $\{\text{RSiO}_{1.5}\}_n$, wherein n equals 8; and at least one chromophore moiety and transparent moiety for use as an *antireflective hardmask composition*.

Thus, Lin, Kennedy, and Feder, alone or in combination, do not disclose or suggest a fully condensed polyhedral oligosilsesquioxane, $\{\text{RSiO}_{1.5}\}_n$, wherein n equals 8; and at least one chromophore moiety and transparent moiety for use as an antireflective hardmask composition, as required by independent claims 1, 21, 30, and 31.

Dependent claims 2-9, 11-15, 17-20, and 22-29 were rejected under 35 U.S.C. §102(b) as allegedly being anticipated by Lin, and under 35 U.S.C. §103(a) as allegedly unpatentable over Kennedy in view of Feder.


Claims 2-9, 11-15, and 17-20, and claims 22-29 are dependent on claims 1 and 21, respectively, and are therefore patentably distinguished over Lin, Kennedy, and Feder (alone or in any combination) because of their dependency from independent claims 1 and 21 for the reasons set forth above, as well as other elements these claims add in combination to their base claim.

Applicants respectfully submit that all of the pending claims, i.e., claims 1-9, 11-15, and 17-31, are in condition for allowance and such favorable action is earnestly solicited.

If any outstanding issues remain, or if the Examiner has any further suggestions for expediting allowance of this application, the Examiner is invited to contact the undersigned at the telephone number indicated below.

The Examiner's attention to this matter is appreciated.

Respectfully submitted,



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